

Docket No. 296428US26PCT



IPW

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF: Tsuyoshi TAKAHASHI, et al.

SERIAL NO: 10/593,254

GAU: 1762

FILED: September 18, 2006

EXAMINER:

FOR: METHOD AND APPARATUS FOR FORMING METAL SILICATE FILM, AND METHOD FOR  
MANUFACTURING SEMICONDUCTOR DEVICE

**INFORMATION DISCLOSURE STATEMENT UNDER 37 CFR 1.97**

COMMISSIONER FOR PATENTS  
ALEXANDRIA, VIRGINIA 22313

SIR:

Applicant(s) wish to disclose the following information.

**REFERENCES**

- The applicant(s) wish to make of record the references cited in the attached International Search Report and listed on the attached form PTO-1449. Copies of the listed references are attached, where required, as are either statements of relevancy or any readily available English translations of pertinent portions of any non-English language references.
- A check or credit card payment form is attached in the amount required under 37 CFR §1.17(p).

**RELATED CASES**

- Attached is a list of applicant's pending application(s), published application(s) or issued patent(s) which may be related to the present application. In accordance with the waiver of 37 CFR 1.98 dated September 21, 2004, copies of the cited pending applications are not provided. Cited published and/or issued patents, if any, are listed on the attached PTO form 1449.
- A check or credit card payment form is attached in the amount required under 37 CFR §1.17(p).

**CERTIFICATION**

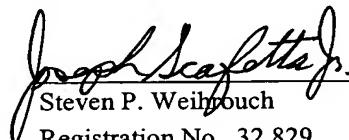
- Each item of information contained in this information disclosure statement was first cited in any communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of this statement.
- No item of information contained in this information disclosure statement was cited in a communication from a foreign patent office in a counterpart foreign application or, to the knowledge of the undersigned, having made reasonable inquiry, was known to any individual designated in 37 CFR §1.56(c) more than three months prior to the filing of this statement.

**DEPOSIT ACCOUNT**

- Please charge any additional fees for the papers being filed herewith and for which no check or credit card payment is enclosed herewith, or credit any overpayment to deposit account number 15-0030. A duplicate copy of this sheet is enclosed.

Respectfully submitted,

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Form PTO 1449 (Modified)		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY DOCKET NO. 296428US26PCT	SERIAL NO. 10/593,254	
		LIST OF REFERENCES CITED BY APPLICANT		APPLICANT Tsuyoshi TAKAHASHI, et al.		
		DEC 18 2006	FILING DATE September 18, 2006	GROUP 1762		
U.S. PATENT DOCUMENTS						
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS
AA		2006/0216953 A1	09/28/06	Shigeru NAKAJIMA, et al.		
AB						
AC						
AD						
AE						
AF						
AG						
AH						
AI						
AJ						
AK						
AL						
AM						
AN						
FOREIGN PATENT DOCUMENTS						
		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION	
AO		2003-297822	10/17/2003	Japan (with English Abstract)	YES	NO X
AP		2004-79687	03/11/2004	Japan (with English Abstract)	YES	NO X
AQ		2002-100627	04/05/2002	Japan (with English Abstract)	YES	NO X
AR		2004-311782	11/04/2004	Japan (Corresponding to US 2006/0216953 A1)	YES	NO X
AS					YES	NO
AT					YES	NO
AU					YES	NO
AV					YES	NO
OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)						
AW	Vishwanathan RANGARAJAN, et al., "Comparison of hafnium silicate thin films on silicon (1 0 0) deposited using thermal and plasma enhanced metal organic chemical vapor deposition", Thin Solid Films 419, 2002, pages 1-4					
AX						
AY						
AZ						<input type="checkbox"/> Additional References sheet(s) attached
Examiner					Date Considered	
*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.						